IN THE CLAIMS

vacuum ultraviolet rays generator from the reactor;

1. (currently amended): A method of fabricating a protective film comprising:
providing a vacuum ultraviolet radiation CVD (Chemical Vapor Deposition) system
comprising a vacuum ultraviolet rays generator, a reactor provided with a platform for
supporting a substrate, a heat retainer provided on the platform, and a window separating the

feeding an organic stock gas from a gas feeder into the reactor while retaining temperature of the substrate at a temperature about equal to or less than 100 °C with the heat retainer; and

irradiating simultaneously the reactor with vacuum ultraviolet rays from the vacuum ultraviolet rays generator through the window;

wherein photons from the vacuum ultraviolet ray generator have a wavelength of about 172 nm and an energy of about 7.2 eV, sufficient to break an Si-N bond.

- 2. (previously presented): A method of fabricating a protective film according to claim 1, wherein retaining of the temperature with the heat retainer is carried out such that the temperature of the substrate is kept at a low temperature in a range of about 25 °C to 100 °C.
- 3. (original): The method of fabricating a protective film according to claim 1, wherein an organosilazane gas having Si-N bonds is used for the organic stock gas.
- 4. (original): The method of fabricating a protective film according to claim 1, further comprising adding an additive gas for increasing nitrogen content in the protective film, or a regulator gas for use in regulating a partial pressure of the organic stock gas in the reactor to the organic stock gas so as to be fed from the gas feeder into the reactor.
 - 5. (canceled)
- 6. (currently amended): The method of fabricating a protective film according to claim [[5]] 1, wherein the step of providing the ultraviolet rays generator includes providing a xenon excimer lamp.

AMENDMENT 10/676,258